

	Hit s	Search Text	DBs
1	2	(immersion near14 lithography) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive) same (source or radiation or light) same (modulat\$4 or (spatial near14 modulat\$4) or SLM) same (mask or photomask or reticle or pattern\$3) same (immersi\$3 near6 (fluid\$4 or liquid or medium)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
2	2	(immersion near14 lithography) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive) same (source or radiation or light) same (mask or photomask or reticle or pattern\$3) same (immersi\$3 near6 (fluid\$4 or liquid or medium))) and (immers\$6 same (modulat\$4 or (spatial near14 modulat\$4) or SLM))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
3	7	(immersion near14 lithography) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive) same (source or radiation or light) same (immersi\$3 near6 (fluid\$4 or liquid or medium))) and (modulat\$4 or (spatial near14 modulat\$4) or SLM) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
4	8	((immersion near14 lithography) or (liquid near9 immersion)) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive) same (source or radiation or light) same (immersi\$3 near6 (fluid\$4 or liquid or medium))) and (modulat\$4 or (spatial near14 modulat\$4) or SLM) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
5	9	((immersion near14 lithography) or (liquid near9 immersion)) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive) same (source or radiation or light) same (immersi\$3 near6 (fluid\$4 or liquid or medium))) and (modulat\$4 or (spatial near14 modulat\$4) or SLM) and pattern\$4	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
6	13	((immersion near14 lithography) or (liquid near9 immersion)) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive) same (immersi\$3 near6 (fluid\$4 or liquid or medium))) and (modulat\$4 or (spatial near14 modulat\$4) or SLM) and (mask or reticle or photomask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
7	19	((immersion near14 lithography) or (liquid near9 immersion)) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive) same (immersi\$3 near6 (fluid\$4 or liquid or medium))) and (modulat\$4 or (spatial near14 modulat\$4) or SLM)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
8	71	((immersion near14 lithography) or (liquid near9 immersion)) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi\$3 near6 (fluid\$4 or liquid or medium))) and (modulat\$4 or (spatial near14 modulat\$4) or SLM) and (expos\$4 or illuminat\$4 or irradiat\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
9	55	((immersion near14 lithography) or (liquid near9 immersion)) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi\$3 near6 (fluid\$4 or liquid or medium))) and (modulat\$4 or (spatial near14 modulat\$4) or SLM) and (expos\$4 or illuminat\$4 or irradiat\$4) and ((mask or reticle or photomask) same pattern\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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10	45	((immersion near14 lithography) or (liquid near9 immersion near14 (system or apparatus))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi\$3 near6 (fluid\$4 or liquid or medium))) and (modulat\$4 or (spatial near14 modulat\$4) or SLM) and (expos\$4 or illuminat\$4 or irradiat\$4) and ((mask or reticle or photomask) same pattern\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
11	3	((immersion near14 lithography) or (liquid near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi\$3 near6 (fluid\$4 or liquid or medium)) same (inlet or input or supply or port)) and (modulat\$4 or (spatial near14 modulat\$4) or SLM) and (expos\$4 or illuminat\$4 or irradiat\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
12	3	((immersion near14 lithography) or (liquid near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi\$3 near6 (fluid\$4 or liquid or medium)) same (inlet or input or supply or port)) and (modulat\$4 or (spatial near14 modulat\$4) or SLM)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
13	59	((immersion near14 lithography) or (liquid near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi\$3 near6 (fluid\$4 or liquid or medium)) same (inlet or input or supply or port))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
14	58	((immersion near14 lithography) or (liquid near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same (immersi\$3 near6 (fluid\$4 or liquid or medium)) same (inlet or input or supply or port)) and (expos\$4 or illuminat\$4 or irradiat\$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
15	1	((immersion near14 lithography) or (liquid near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same ((fluid\$4 or liquid or medium) near18 (inlet or input or supply or port) near12 (fibrous or porous or filter\$4 or \$3strain\$4))) and (modulat\$4 or (spatial near14 modulat\$4) or SLM or deflect\$4 or acousto\$6)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

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16	3	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and ((substrate or wafer or workpiece) same ((fluid\$4 or liquid or medium or water) near18 (inlet or input or supply or port)) same (fibrous or porous or filter\$4 or \$3strain\$4)) and (modulat\$4 or (spatial near14 modulat\$4) or SLM or deflect\$4 or acousto\$6) and (immers\$4 near9 (liquid or fluid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
17	129	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and (modulat\$4 or (spatial near14 modulat\$4) or SLM or deflect\$4 or acousto\$6) and (immers\$4 near9 (liquid or fluid))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hit s	Search Text	DBs
18	12	((immersion near14 lithography) or ((liquid or fluid) near9 immersion near14 (system or apparatus or method))) and ((workpiece or substrate or wafer) same (photosensitive or (light\$3 near5 sensitive) or photoresist or resist or sensitive)) and ((modulat\$4 or (spatial near14 modulat\$4) or SLM or deflect\$4 or acousto\$6) same (immers\$4 near9 (liquid or fluid)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB